

FIG. 1

Vfb (V) vs. TOX (A) for Al/20A\_TiN Gate

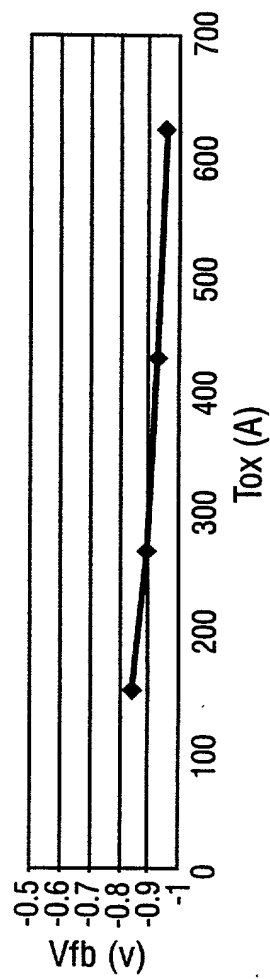


FIG. 2

Work-Function of Al/TiN Gate Changes  
as the thickness of thin TiN changes

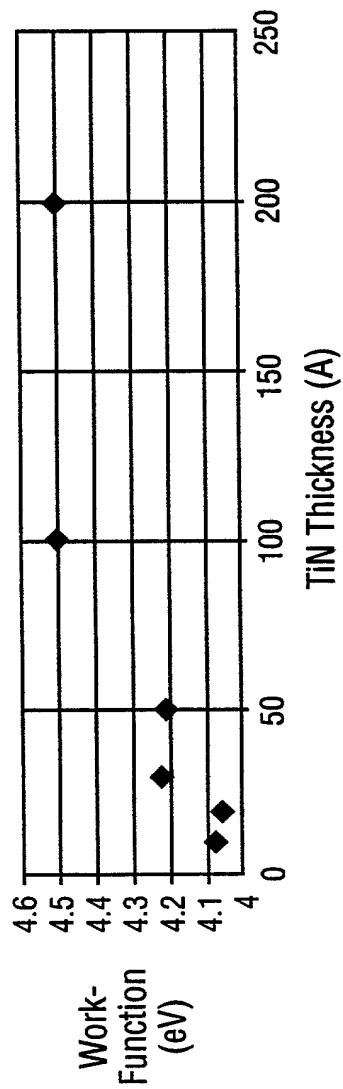


FIG. 3

$V_t$  for various gate stack with different TiN thickness

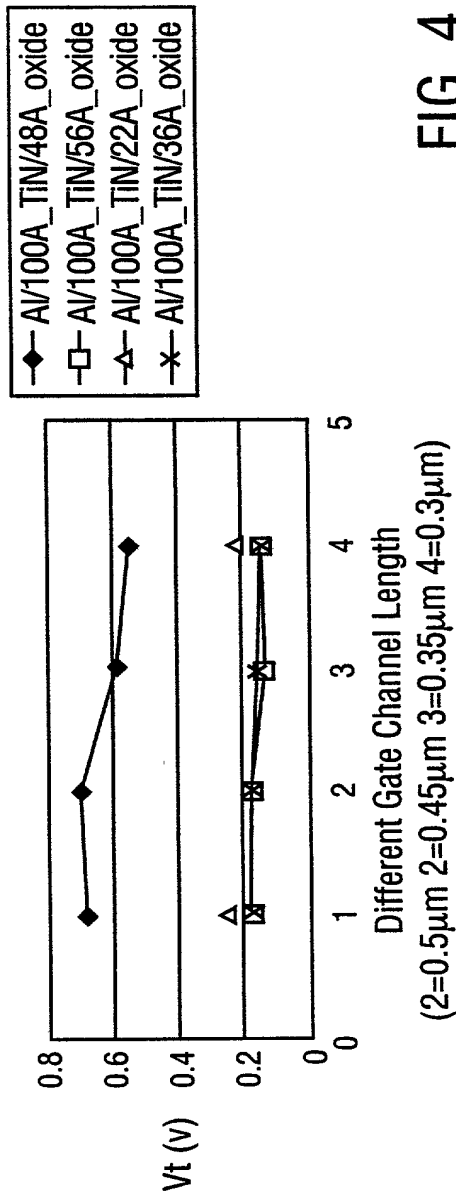


FIG. 4

Gate Leakage (Am p/cm 2) vs. Gate Voltage (V)  
 $T_{ox} = 22\text{\AA}$

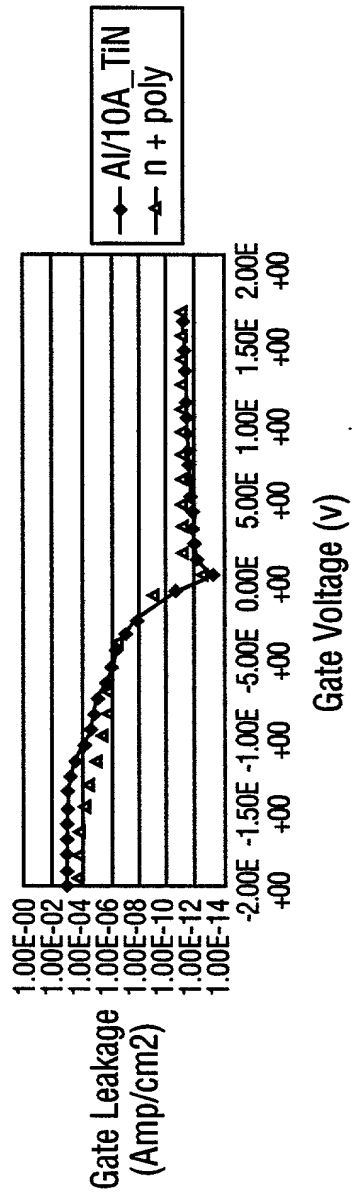


FIG. 5

QuasiStatic/High Frequency Capacitor Voltage  
Curves for A1/20 A\_TIN/50A Oxide  
Gate Stack

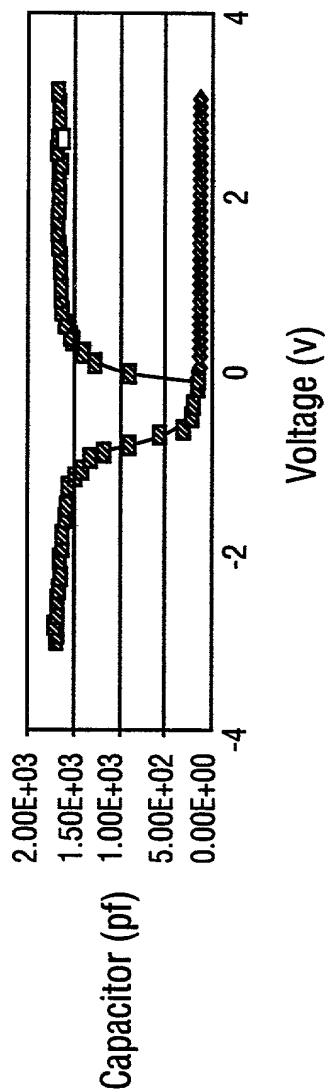


FIG. 6

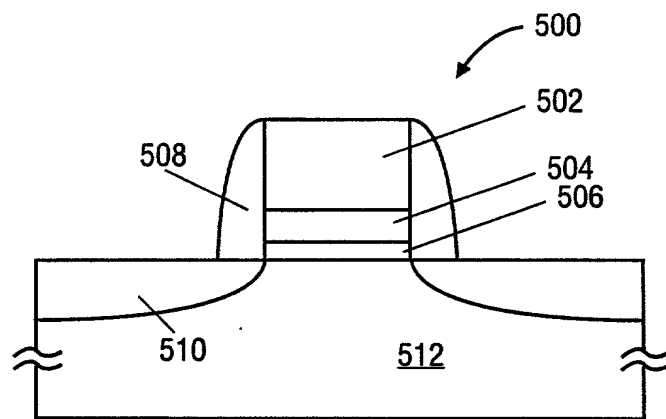


FIG. 7

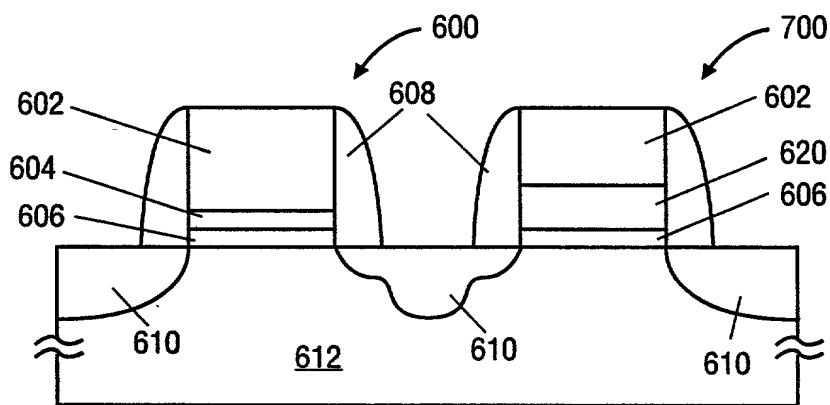


FIG. 8